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| APPLICATION NO. | FILING DATE | FIRST NAMED INVENTOR | ATTORNEY DOCKET NO. | CONFIRMATION NO. | |
|---|-----------------|----------------------|---------------------|------------------|--|
| 10/664,355 | 09/17/2003 | Masumi Suetsugu | 2185-0698P | 8070 | |
| 2292 | 7590 02/08/2006 | | EXAM | EXAMINER | |
| BIRCH STEWART KOLASCH & BIRCH | | | ASHTON, ROSEMARY E | | |
| PO BOX 747 FALLS CHURCH, VA 22040-0747 | | | ART UNIT | PAPER NUMBER | |
| | | | 1752 | _ | |

DATE MAILED: 02/08/2006

Please find below and/or attached an Office communication concerning this application or proceeding.

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|---|---|---|----|
| | Application No. | Applicant(s) | |
| | 10/664,355 | SUETSUGU ET AL | |
| Office Action Summary | Examiner | Art Unit | |
| | Rosemary E. Ashton | 1752 | |
| The MAILING DATE of this communication ap Period for Reply | pears on the cover sheet with the | e correspondence address | |
| A SHORTENED STATUTORY PERIOD FOR REPL WHICHEVER IS LONGER, FROM THE MAILING D. - Extensions of time may be available under the provisions of 37 CFR 1. after SIX (6) MONTHS from the mailing date of this communication. - If NO period for reply is specified above, the maximum statutory period. - Failure to reply within the set or extended period for reply will, by statut Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b). | DATE OF THIS COMMUNICATE 136(a). In no event, however, may a reply be will apply and will expire SIX (6) MONTHS frice, cause the application to become ABANDO | ON. It timely filed om the mailing date of this communication. NED (35 U.S.C. § 133). | |
| Status | | | |
| 1) ☐ Responsive to communication(s) filed on 13 (2a) ☐ This action is FINAL . 2b) ☐ This 3) ☐ Since this application is in condition for allowed closed in accordance with the practice under | s action is non-final. ance except for formal matters, p | | |
| Disposition of Claims | | | |
| 4) ☐ Claim(s) 1,2,5,7 and 9-13 is/are pending in the 4a) Of the above claim(s) is/are withdra 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 1,2,5,9-11 and 13 is/are rejected. 7) ☐ Claim(s) 7 and 12 is/are objected to. 8) ☐ Claim(s) are subject to restriction and/or are subjected to by the Examine 10) ☐ The drawing(s) filed on is/are: a) ☐ accompanies to the formula of t | awn from consideration. or election requirement. er. cepted or b) objected to by th | | |
| Applicant may not request that any objection to the Replacement drawing sheet(s) including the correct 11) The oath or declaration is objected to by the E | ction is required if the drawing(s) is | objected to. See 37 CFR 1.121(d). | |
| Priority under 35 U.S.C. § 119 | | | |
| 12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority documen 2. Certified copies of the priority documen 3. Copies of the certified copies of the priority documen application from the International Burea * See the attached detailed Office action for a list | ts have been received. ts have been received in Applicate the prity documents have been receing (PCT Rule 17.2(a)). | ation No. <u>09/559,646</u> . ived in this National Stage | |
| Attachment(s) 1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date 8/10/05. | 4) Interview Summa Paper No(s)/Mail) S) Notice of Informa 6) Other: | | |

DETAILED ACTION

Claim Rejections - 35 USC § 103

- 1. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 2. Claims 1,2,5,9-11,13 are rejected under 35 U.S.C. 103(a) as being unpatentable over Urano et al. patent no. 5,695,910 in view of Niki et al patent no. 5,744,281 and Zampini et al. patent no. 6,858,379.

Urano teaches a negative resist composition comprising a polyvinyl phenol based resin in which the phenolic hydroxyl group is partially alkyl etherified, a photo-acid generator (PAG), a crosslinker and it may also have a basic nitrogen compound such as pyridine (col. 12, lines 1-15). Examples of the resin are shown in col. 4 and include the ether groups such as ethoxyethoxystyrene, methoxyethoxystyrene and isopropyloxy-ethoxystyrene.

Urano does not teach the composition contains the dipyridyl compounds claimed.

Niki teaches a photoresist composition comprising a resin, PAG and a basic nitrogen compound. The preferred nitrogen compound is a pyridine compound such as 1,2-bis(4-pyridyl)ethane, and 1,2-bis(2-pyridyl)ethylene. These compounds meet the

limitations of A in formula 1 in claim 1 when A is a bivalent hydrocarbon residue of an ethane (-CH2-CH2-) and an ethylene (-CH=CH-).

It would have been obvious to one of ordinary skill in the art to use bis(4-pyridyl)ethane or 1,2-bis(2-pyridyl)ethylene as the basic nitrogen compounds in the invention of Urano because, as taught in col. 2, lines 39-45 of Zampini, a basic additive can enhance_resolution of an image pattern formed with the_resist, particularly by inhibiting undesired diffusion of photogenerated acid into unexposed resist layer regions.

3. Claim 9 is rejected under 35 U.S.C. 103(a) as being unpatentable over Urano et al. patent no. 5,695,910 in view of Niki et al patent no. 5,744,281 and Zampini et al. patent no. 6,858,379 as applied to claim 1 above, and further in view of Huang et al. patent no. 5,712,078 and Renner patent no. 4371,605.

In col. 8 and 9 Urano teaches the resist composition comprises a PAG selected from the group consisting of disulfones, sulfonyl-alphaketo-diazomethanes, triarylsulfonium and nitrobenzyl compounds.

It does not teach the PAG is a sulfonic ester of an N-hydroxyimide compound.

An N-hydroxyimide is shown below.

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(v) Sulfonic Acid Esters of N-hydroxyimide Compounds of Formula (P5)

From col.27 of Pat.no. 6,916,592 1

In col. 7 Huang teaches PAG compounds for photoresist compositions wherein the PAG compounds are selected from the group consisting of metallic, metalloid, and non-metallic onium salts of which examples are described in U.S. Pat. No. 4,102,687, aryl sulfonates including without limitation, tris-pyrogallol sulfonates and anthracene-2-sulfonates such as 9,10-diethylanthracene-2-sulfonate, 2-nitrobenzyl esters, beta-ketosulfones, disulfones, arylsulfonyl-alpha-keto- and alpha-carboxyl-diazomethanes, and precursors of substituted and unsubstituted sulfonic acids, including, without limitation, oxime sulfonates as described in EP 0 361 907 to Hoechst Celanese Corporation, and in the publication of Shirai, et al., "Synthesis and Photo-Induced Dissolution of Polymers Bearing Imino Sulfonate Groups," J. Polym. Sci. A, 27, 325 (1989), and N-hydroxyimides of the type described in U.S. Pat. No. 4,371,605. Huang exemplifies exposure at 248 nm using a triphenylsulfonium salt in example 15.

U.S. Pat. No. 4,371,605, cited in Huang, is to Renner and teaches photopolymerizable compositions have a PAG containing sulfonic acid esters of N-

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hydroxyamides and N-hydroxyimides as photoinitiators (col. 1) as claimed in claim 9 of the instant application.

It would have been obvious to one of ordinary skill in the art to use a sulfonic acid ester of N-hydroxyimides as a PAG in the invention of Urano with a reasonable expectation of obtaining a pattern upon exposure to 248 nm because Huang equates the sulfonic acid ester of N-hydroxyimides with the PAG's taught in Urano, such as onium salts, disulfones, arylsulfonyl-alphaketo-diazomethane and nitrobenzyl compounds and both Urano (Ex.1, col. 23) and Huang (Ex.15, col. 17) use 248 nm light for successful image formation.

Allowable Subject Matter

- 4. Claims 7,12 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.
- 5. The following is a statement of reasons for the indication of allowable subject matter: The prior art does not teach a negative resist composition having a dipyridylsulfide or dipyridyldisulfide compound.

Conclusion

6. Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

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A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

7. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Rosemary E. Ashton whose telephone number is 571-272-1326. The examiner can normally be reached on Mon-Fri, 11:00-5:00.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Cynthia Kelly can be reached on 571-272-1526. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR.

Status information for unpublished applications is available through Private PAIR only.

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Rosemary E. Ashton Primary Examiner Art Unit 1752

February 2, 2006 rea

ROSEMARY ASHTON PRIMARY EXAMINER